Notice of Allowability	Application No.	Application No. Applicant(s)	
	09/767,558	MELUCH ET AL.	
	Examiner	Art Unit	
	Ana M Fortuna	1723	
The MAILING DATE of this communication and All claims being allowable, PROSECUTION ON THE MERITS herewith (or previously mailed), a Notice of Allowance (PTOLNOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT of the Office or upon petition by the applicant. See 37 CFR 1.1. This communication is responsive to 12/15/03.	ilS (OR REMAINS) CLOSED in 85) or other appropriate comm RIGHTS. This application is :	n this application. If not included unication will be mailed in due course. THIS	S ative
2. The allowed claim(s) is/are <u>19,20 and 22-37</u> .			
3. The drawings filed on 22 January 2001 are accepted by			
4. ☐ Acknowledgment is made of a claim for foreign priority a) ☐ All b) ☐ Some* c) ☐ None of the: 1. ☐ Certified copies of the priority documents h 2. ☐ Certified copies of the priority documents h 3. ☐ Copies of the certified copies of the priority International Bureau (PCT Rule 17.2(a)). * Certified copies not received: Applicant has THREE MONTHS FROM THE "MAILING DAT noted below. Failure to timely comply will result in ABANDO THIS THREE-MONTH PERIOD IS NOT EXTENDABLE. 5. ☐ A SUBSTITUTE OATH OR DECLARATION must be su INFORMAL PATENT APPLICATION (PTO-152) which (a) ☐ including changes required by the Notice of Draftsp 1) ☐ hereto or 2) ☐ to Paper No./Mail Date (b) ☐ including changes required by the attached Examin Paper No./Mail Date Identifying indicia such as the application number (see 37 CF) each sheet. Replacement sheet(s) should be labeled as such attached Examiner's comment regarding REQUIREMENT.	rave been received. Place been received in Application of documents have been received in Application of the Power of this communication to fill of the Power of this application. Place of this communication to fill of the Power of this application. Place of this application of the place of the pla	on No In this national stage application from the din this national stage application from the a reply complying with the requirements AMINER'S AMENDMENT or NOTICE OF declaration is deficient. In the Office action of the drawings in the front (not the back) of R 1.121(d). ERIAL must be submitted. Note the	
 Attachment(s) 1. Notice of References Cited (PTO-892) 2. Notice of Draftperson's Patent Drawing Review (PTO-94) 3. Information Disclosure Statements (PTO-1449 or PTO/S Paper No./Mail Date	8) 6. ☐ Interview St Paper No./ B/08), 7. ☒ Examiner's	formal Patent Application (PTO-152) Jammary (PTO-413), Mail Date Amendment/Comment Statement of Reasons for Allowance Ana M Fortuna Primary Examiner Art Unit: 1723	

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EXAMINER'S AMENDMENT/REASONS FOR ALLOWANCE

1. An examiner's amendment to the record appears below. Should the changes and/or additions be unacceptable to applicant, an amendment may be filed as provided by 37 CFR 1.312. To ensure consideration of such an amendment, it MUST be submitted no later than the payment of the issue fee.

Authorization for this examiner's amendment was given in a telephone interview with Thomas C. Basso on 5/03/04.

Amend claim 19.

19. (Amended) A Melt-spun polysulfone semipermeable membrane, the melt-spun polysulfone semipermeable membrane consisting essentially of a polysulfone compound and a solvent for the polysulfone compound wherein the melt-spun polysulfone semipermeable membrane has a homogeneous structure such that the melt-spun polysulfone semipermeable membrane has a substantially uniform pore structure through a thickness of the melt-spun polysulfone semipermeable membrane; wherein the solvent is selected from the group consisting of tetramethylene sulfone, antipyridine, -valerolactam, diethylphthalate, and mixtures thereof.

Cancel claim 21.

2. The following is an examiner's statement of reasons for allowance: claims 19-20, and 22-37 are allowed over the prior art of record. The prior art of record teach membranes polysulfone membrane with homogeneous pores through the structure, however the membranes are not made from the composition and process as claimed. Melt-spun includes a melting step of the mixture of polymer and solvent and or non-

solvent follow by extrusion and quenching to form the pores on the membrane. Based on the process, the membranes properties in addition to the pores are expected to be distinct from a membrane made by wet or dry spinning process, or from membranes by a distinct polymer/solvent mixture. Kopp et al teach melt-spun polysulfone membrane including microporous surface and through out the thickness of the membrane, however, the listed solvents claimed is not suggested; the addition of non-solvents is also no suggested in the patent.

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Ana M Fortuna whose telephone number is (571) 272-1141. The examiner can normally be reached on 9:30-6:00 M-F.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Wanda L. Walker can be reached on (571) 272-1151. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

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Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Ana M Fortuna Primary Examiner Art Unit 1723

AF May 03, 2004